

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant | : | Hada et al. |
| Appl. No. | : | 10/557,694 |
| Filed | : | November 22, 2005 |
| For | : | RESIN FOR PHOTORESIST COMPOSITION, PHOTORESIST COMPOSITION AND METHOD FOR FORMING RESIST PATTERN |
| Examiner | : | Eoff, A. |
| Group Art Unit | : | 1795 |

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION**Mail Stop AF**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **November 19, 2007**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.